

FIG. 1

FIG. 2

THICKNESS OF CHEMICAL OXIDE FILM ON SILICON WAFER SURFACE (nm)  
TREATMENT TIME WITH OZONIZED WATER (sec)

FIG. 3

SC-1 CLEANING

OZONIZED WATER TREATMENT + HYDROFLUORIC ACID CLEANING

EXISTENCE RATIO OF Si ATOM COORDINATION NUMBER (%)

TIME PASSAGE SINCE CLEANING (hr)

FIG. 4

FIG. 5

HYDROGEN ANNEALING

OZONIZED WATER/HF CLEANING

SC-1 CLEANING

SPATIAL FREQUENCY (/μm)

FIG. 6

HYDROGEN ANNEALING

OZONIZED WATER CLEANING

EXTRAPURE WATER CLEANING

SPATIAL FREQUENCY (/μm)

Fig.1

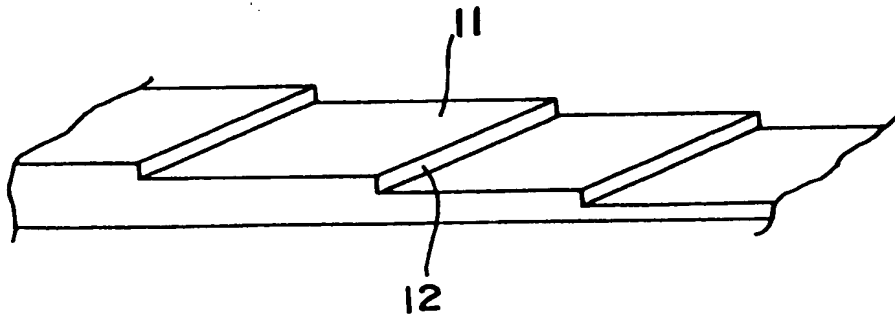


Fig.2

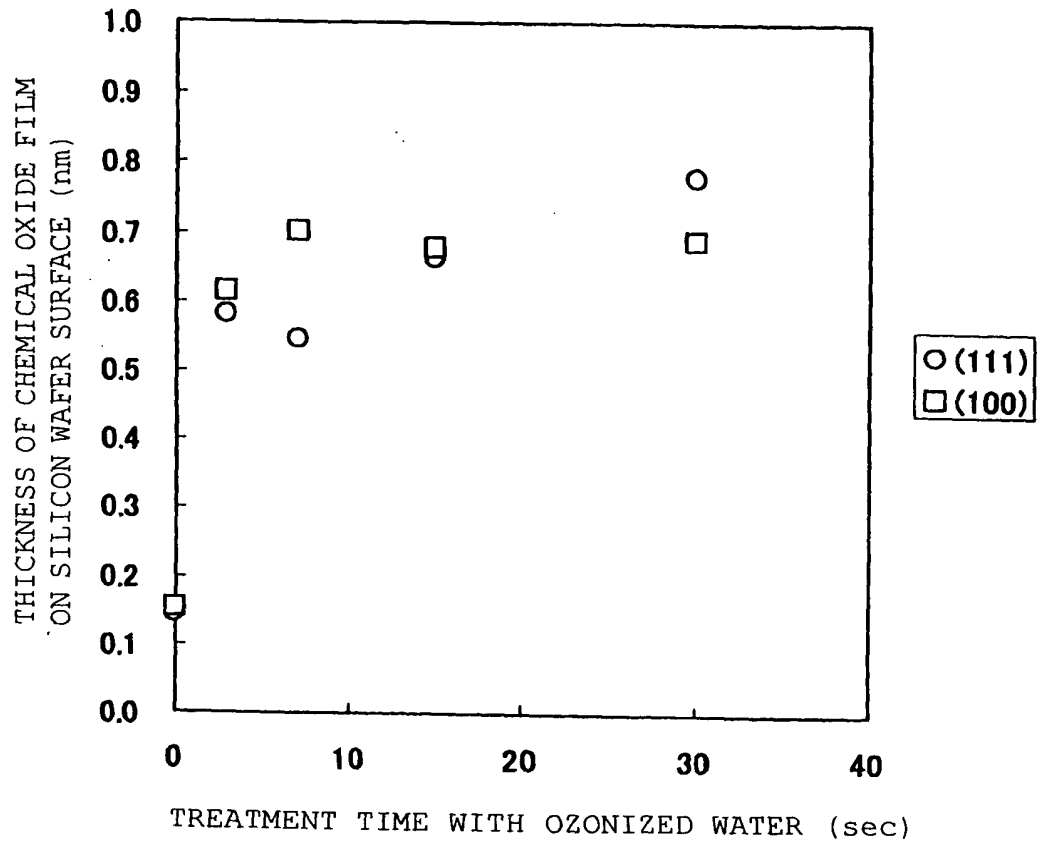


Fig. 3

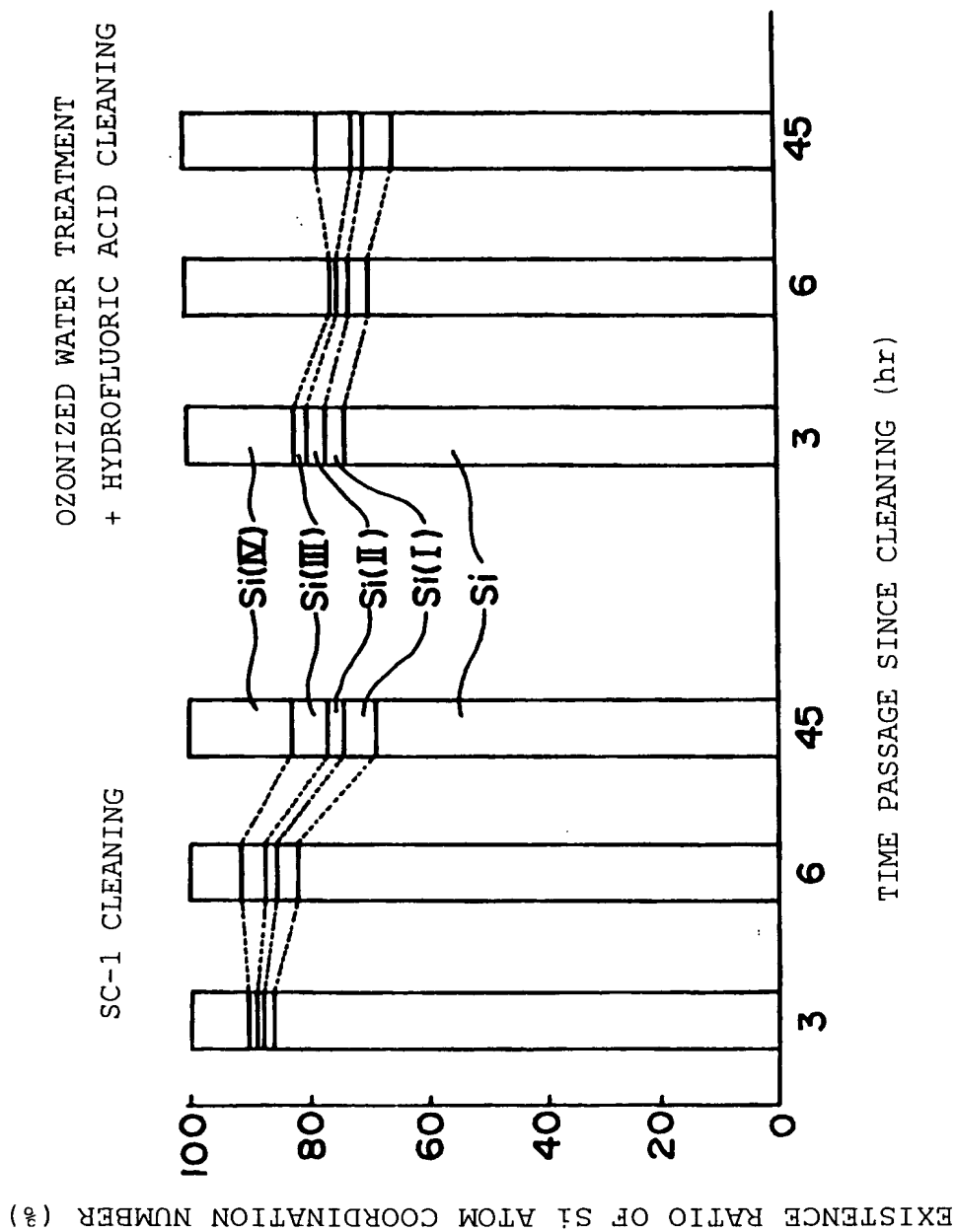


Fig.4

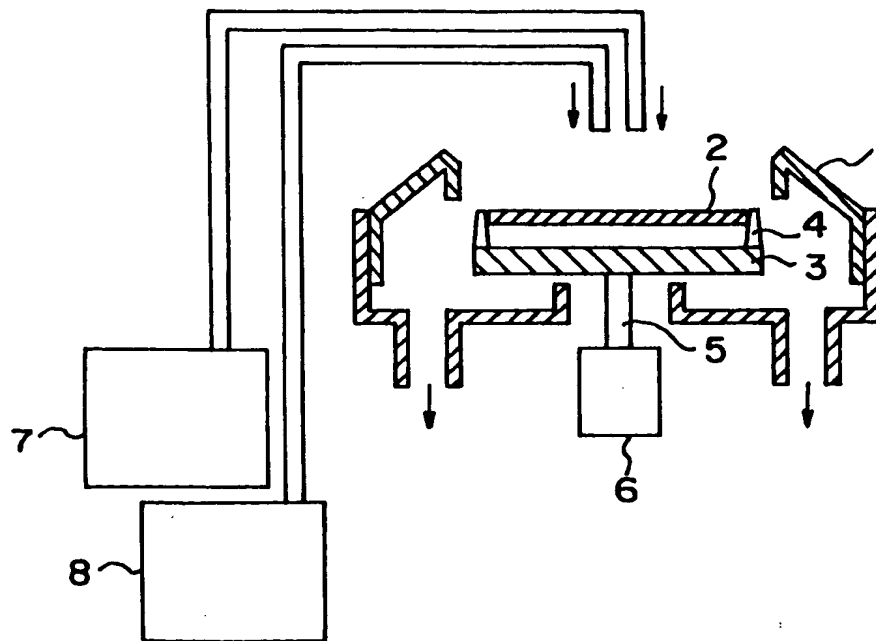


Fig.5

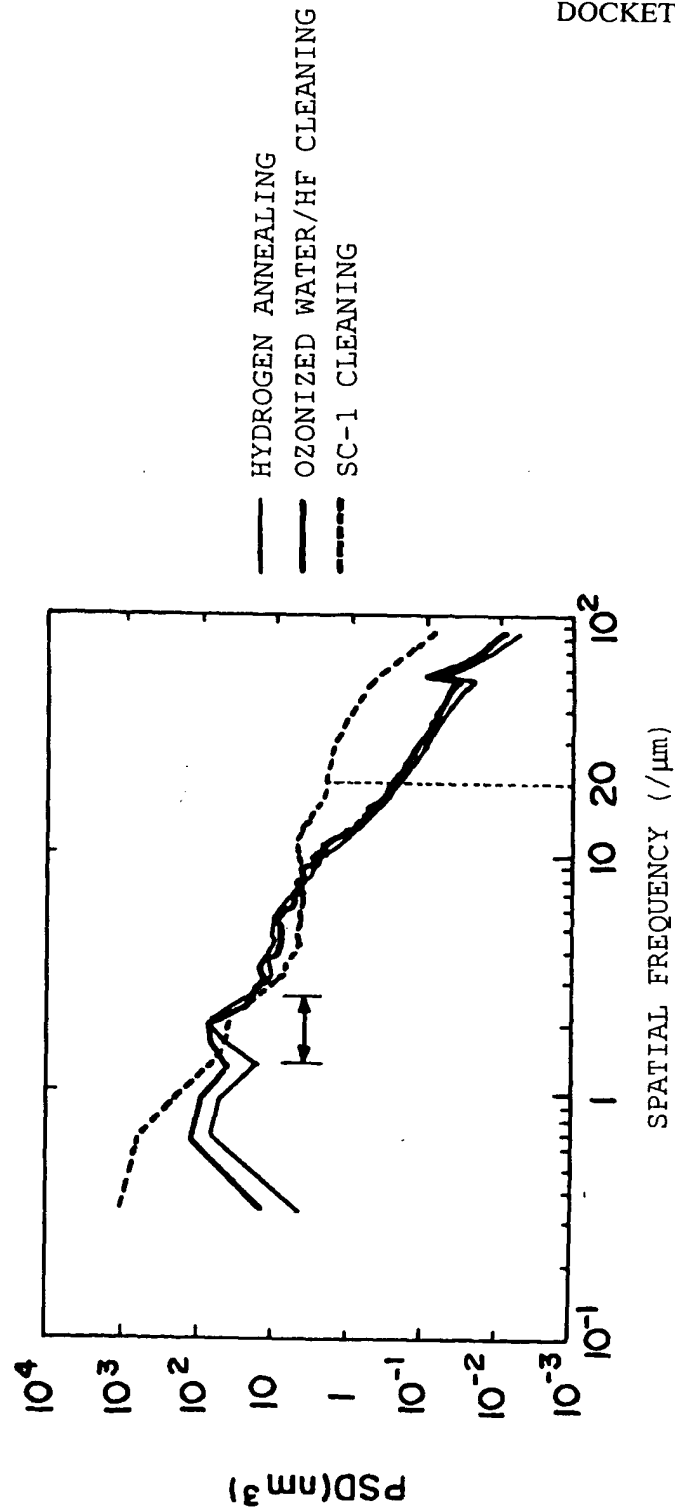


Fig. 6

